Micropatterning Japan TC
Meeting Summary and Minutes

SEMI Japan Standards Winter 2015 Meetings
Thursday, January 29, 2015, 15:30-17:00
SEMI Japan, Tokyo, Japan

Next Committee Meeting
SEMI Japan Standards Summer 2015 Meetings
Thursday, June 25, 2015, 15:30-17:00
SEMI Japan, Tokyo, Japan

Table 1 Meeting Attendees
Co-Chairs: Morihisa Hoga (Dai Nippon Printing)
SEMI Staff: Naoko Tejima (SEMI Japan)

<table>
<thead>
<tr>
<th>Company</th>
<th>Last</th>
<th>First</th>
<th>Company</th>
<th>Last</th>
<th>First</th>
</tr>
</thead>
<tbody>
<tr>
<td>Dai Nippon Printing</td>
<td>Hoga</td>
<td>Morihisa</td>
<td>Dai Nippon Printing</td>
<td>Suzuki</td>
<td>Toshio</td>
</tr>
<tr>
<td>-</td>
<td>Otaki</td>
<td>Masao</td>
<td>SEMI Japan</td>
<td>Tejima</td>
<td>Naoko</td>
</tr>
</tbody>
</table>

*alphabetical order by last name

Table 2 Leadership Changes
None

Table 3 Ballot Results
None

Table 4 Authorized Ballots

<table>
<thead>
<tr>
<th>#</th>
<th>When</th>
<th>SC/TF/WG</th>
<th>Details</th>
</tr>
</thead>
<tbody>
<tr>
<td>5229A</td>
<td>Cycle 4</td>
<td>Mask Data Format for Mask Tools Task Force</td>
<td>Revision to SEMI P44-0211, Specification for Open Artwork System interchange Standard (OASIS®) Specific to Mask Tools</td>
</tr>
</tbody>
</table>

Table 5 Authorized Activities

<table>
<thead>
<tr>
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<th>Type</th>
<th>SC/TF/WG</th>
<th>Details</th>
</tr>
</thead>
<tbody>
<tr>
<td>5229A</td>
<td>Information (Blue) Ballot</td>
<td>Mask Data Format for Mask Tools Task Force</td>
<td>Revision to SEMI P44-0211, Specification for Open Artwork System interchange Standard (OASIS®) Specific to Mask Tools</td>
</tr>
</tbody>
</table>
Table 6 New Action Items

<table>
<thead>
<tr>
<th>Item #</th>
<th>Assigned to</th>
<th>Details</th>
</tr>
</thead>
<tbody>
<tr>
<td>MP120828-2</td>
<td>5 Year Review Task Force</td>
<td>To draft the document of Doc. 5484, Revision to SEMI P22-0307 to submit it for the earliest possible cycle.</td>
</tr>
<tr>
<td>MP121211-1</td>
<td>5 Year Review Task Force</td>
<td>To draft the document of Doc. 5537, Line Item Revision to SEMI P23-0200 to submit it for the earliest possible cycle.</td>
</tr>
<tr>
<td>MP130828-1</td>
<td>5 Year Review Task Force</td>
<td>To draft the background statements for the Document #5484 and #5537</td>
</tr>
</tbody>
</table>

1 Welcome, Reminders and Introductions

Morihisa Hoga, committee co-chair, called the meeting to order at 15:30. Self-introductions were made followed by the agenda review.

2 Required Meeting Elements

The meeting reminders on program membership requirement, antitrust issues, intellectual property issues and international effective meeting guidelines, were reviewed by SEMI staff, Naoko Tejima.

3 Review of Previous Meeting Minutes

The committee reviewed the minutes of the previous meeting held on October 8, 2014.

Motion: To approve the minutes of the previous meeting as submitted.
By / 2nd: Toshio Suzuki (Dainippon Printing) / Masako Otaki (-)
Discussion: None
Vote: 2 in favor and 0 opposed. Motion passed.
Attachment: 01_JA_Micropatterning_Previous_Mtg_Minutes_150129

4 SEMI Staff Report

Attachment: 02_SEMI_Staff_Report_150129

5 Liaison Reports

5.1 Microlithography North America TC Report

Naoko Tejima briefly reported for the Microlithography North America TC. This report included Task Force and Leadership Changes, Leadership, Microlithography TC Chapter Structure, Meeting Information, Document Review Summary, New Activities, Task Force Updates, Five-year Review Status and Contact Information.
Attachment: 03_Microlithography_NA_TC_Report_Jan2015_150129
6 Task Force Reports

6.1 Mask Data Format for Mask Tools Task Force

Toshio Suzuki reported for the Mask Data Format for Mask Tools Task Force. Of note:

- Doc.#5229, Revision to SEMI P44-0211, Specification for Open Artwork System interchange Standard (OASIS®) Specific to Mask Tools, failed the ISC A&R Subcommittee for procedural review, and was returned to the TF.

- Doc.#5229A, Revision to SEMI P44-0211, Specification for Open Artwork System interchange Standard (OASIS®) Specific to Mask Tools, will be submitted the information ballot from the middle of February to the middle of March before the letter ballot.

Motion: To submit the information ballot of Doc.#5229A, Revision to SEMI P44-0211, Specification for Open Artwork System interchange Standard (OASIS®) Specific to Mask Tools. from the middle of February to the middle of March.

By / 2nd: Toshio Suzuki (Dainippon Printing) / Masako Otaki (-)

Discussion: None

Vote: 2 in favor and 0 opposed. **Motion passed.**


By / 2nd: Toshio Suzuki (Dainippon Printing) / Masako Otaki (-)

Discussion: None

Vote: 2 in favor and 0 opposed. **Motion passed.**

Motion: To approve to extend the activity duration of SNARF 5229 & 5366.

By / 2nd: Toshio Suzuki (Dainippon Printing) / Masako Otaki (-)

Discussion: None

Vote: 2 in favor and 0 opposed. **Motion passed.**

6.2 5 Year Review Task Force

Masao Otaki reported on progress for the 5 Year Review Task Force. Of note:

- Task Force is working for the below 2 documents, however, since the activities is not critical, it may should be aborted. TF leader will make a decision until the next meeting.
  - Doc.#5484, Revision to SEMI P22-0307, Guideline for Photomask Defect Classification and Size Definition.
  - Doc.#5537, Line Item Revision to SEMI P23-0200 (Reapproved 1107), Guidelines for Programmed Defect Masks and Benchmark Procedures for Sensitivity Analysis of Mask Defect Inspection Systems.
7 Old Business

7.1 Previous Meeting Action Items
Naoko Tejima reviewed the previous meeting action items.

Table 7 Previous Meeting Actions Items

<table>
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<tr>
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<tr>
<td>MP120828-2</td>
<td>5 Year Review Task Force</td>
<td>To draft the document of Doc. 5484, Revision to SEMI P22-0307 to submit it for the earliest possible cycle. … Open</td>
</tr>
<tr>
<td>MP121211-1</td>
<td>5 Year Review Task Force</td>
<td>To draft the document of Doc. 5537, Line Item Revision to SEMI P23-0200 to submit it for the earliest possible cycle. … Open</td>
</tr>
<tr>
<td>MP130828-1</td>
<td>5 Year Review Task Force</td>
<td>To draft the background statements for the Document #5484 and #5537. … Open</td>
</tr>
<tr>
<td>MP141008-1</td>
<td>SEMI Staff</td>
<td>To forward adjudication result of Doc.#5229 to the ISC A&amp;R Subcommittee for procedural review… … Close</td>
</tr>
</tbody>
</table>

8 New Business
None

9 Action Item Review

9.1 New Action Items
Naoko Tejima reviewed the new action items. These can be found in the New Action Items table at the beginning of these minutes.

10 Next Meeting and Adjournment
The next meeting of the Micropatterning Japan TC meeting is scheduled for Thursday, June 25, 2015, 15:30-17:00, at SEMI Japan, Tokyo, Japan.
Respectfully submitted by:
Naoko Tejima
Manager, Standards
SEMI Japan
Phone: +81.3.3222.5804
Email: ntejima@semi.org

Minutes approved by:

| Morihisa Hoga (Dai Nippon Printing), Co-chair | April **, 2015 |

Table 8 Index of Available Attachments

<table>
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<tr>
<th>#</th>
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</thead>
<tbody>
<tr>
<td>1</td>
<td>JA_Micropatterning_Previous_Mtg_Minutes_150129</td>
</tr>
<tr>
<td>2</td>
<td>SEMI_Staff_Report_150129</td>
</tr>
<tr>
<td>3</td>
<td>Microlithography_NA_TC_Report_Jan2015_150129</td>
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#1 Due to file size and delivery issues, attachments must be downloaded separately. A .zip file containing all attachments for these minutes is available at www.semi.org. For additional information or to obtain individual attachments, please contact Naoko Tejima at the contact information above.